

ABSTRACT

A method for manufacturing a mask blank by depositing a film of a resist liquid on a substrate having a thin film functioning as a transfer pattern by a spin-coating process, covering the substrate with a covering member, and performing removal by dissolving of an unnecessary part of the resist film by supplying a solvent from above the covering member during the rotation of the substrate and the covering member together so that the solvent is supplied to the periphery of the substrate, wherein a reduced-pressure-drying process for the resist film deposited by the spin-coating process is performed before the unnecessary-film-removing process of removing the unnecessary part of the resist film by dissolving so that a deterioration in the within-film thickness uniformity of the resist film caused by the unnecessary-film-removing process is suppressed.